



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: >90%CA
3. SURFACE QUALITY(S1, S2): 60/40(S/D)
4. WAVEFRONT ERROR(RMS): $\lambda / 4 @ 633 \text{ nm}$ (SUBSTRATE)
5. PARALLELISM(S1, S2): <3 arcmin
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:
 FILTERING(S1): $T_{\text{avg}} > 90\%$, $T_{\text{abs}} > 85\% @ 380-410 \text{ nm}$, 45° AOI
 $R_{\text{avg}} > 95\%$, $R_{\text{abs}} > 90\% @ 440-800 \text{ nm}$, 45° AOI
 AR COATING(S2): $R_{\text{abs}} < 2\% @ 380-410 \text{ nm}$, 45° AOI

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|--|--------|--------------|---|--------|-------|-----|
| DRAWING PROJECTION | | | LBTEK | | | |
| | NAME | DATE | DM10-425SP | | | |
| DRAWN | LZHOU | JUL./30th/24 | SHORTWAVE DICHOIC MIRROR $\text{Ø} 25.4 \text{ mm} \times 3.2 \text{ mm}$, 425 nm | | | |
| APPROVAL | WCHENG | JUL./30th/24 | MATERIAL | WEIGHT | SCALE | REV |
| FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES | | | UVFS | 3.6 g | 2:1 | A |